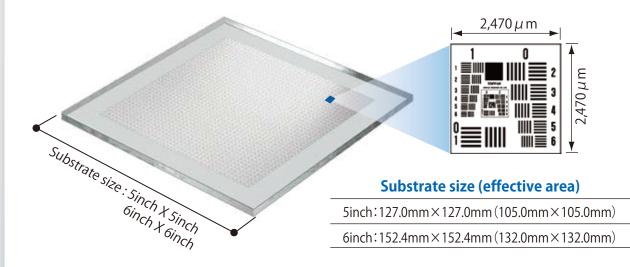


## For precision management, the resolution confirmation of the device

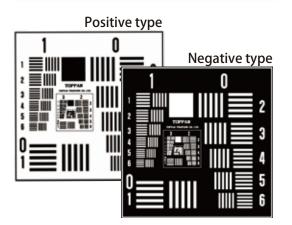
## **TOPPAN TEST CHART**

It is the photomask which formed the basic-shaped pattern with chromium on the high purity glass substrate.

We prepare for a positive type mask and a negative type mask. It is available in the uses such as accuracy management of equipment, a resolution check, and a valuation basis at photoresist selection.



Pattern: No.1



Positive type Negative type

Pattern: No.2

In addition to the above standard products, we can also produce custom models.

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